

Figure 1 Tantalum (carbo)nitride resistivity data obtained by four-point probe measurements for various RF substrate bias power values, indicating a stark decrease in resistivity due to substrate bias application. The black curve serves as a guide to the eye. All samples were prepared using 330 PEALD cycles, of which the precursor and plasma are illustrated, and the DC bias voltages and resulting thicknesses are labelled.

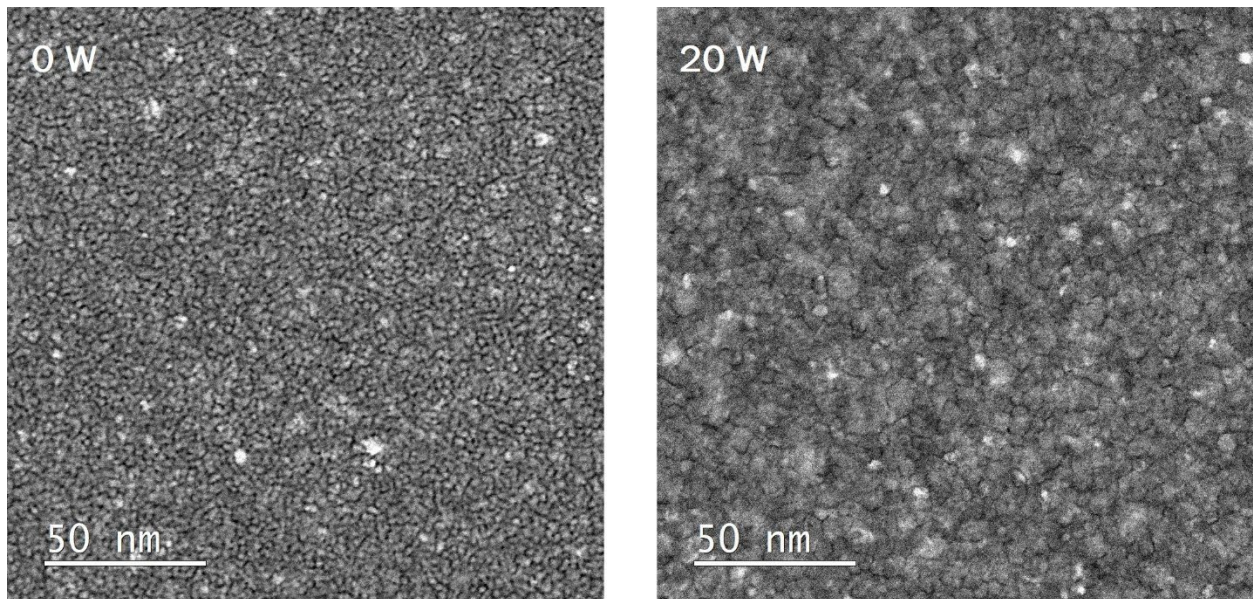


Figure 2 HAADF-STEM images revealing an increase in grain size when applying an RF substrate bias.